

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hojo et al.
Appl. No. : 10/554,380
Filed : October 26, 2005
For : POSITIVE PHOTORESIST
COMPOSITION AND METHOD
FOR FORMING RESIST
PATTERN
Examiner : A. Eoff
Group Art Unit : 1753

OK TO ENTER: /A.E./

04/22/2008

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **January 11, 2008**, Applicants respectfully request the Examiner to enter the following amendments and consider the following remarks.

Amendments to the claims are reflected in the **listing of claims** which begins on page 2 of this paper.

Remarks begin on page 5 of this paper.